

**PATTERN FORMING METHOD, PHOTSENSITIVE RESIN COMPOSITION,
CURED FILM, LAMINATE, AND DEVICE**

ABSTRACT

There is provided a pattern forming method that includes an exposure step of exposing a photosensitive film to laser light; and a development step of developing the photosensitive film after the exposure to obtain a pattern, where the photosensitive film contains at least one precursor selected from the group consisting of a polyimide precursor and a polybenzoxazole precursor, and an onium salt.

Figure 1